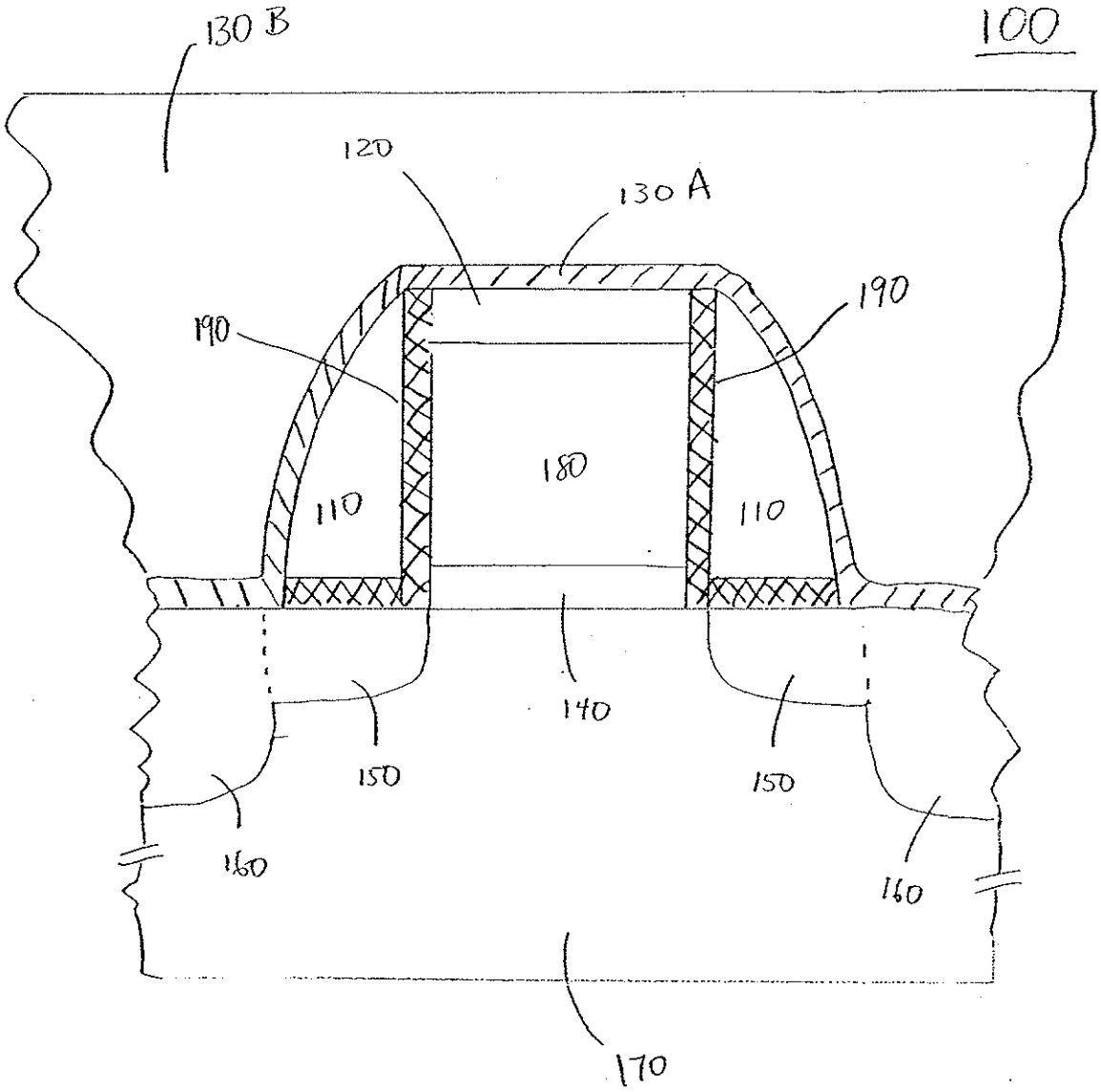


FIG. 1

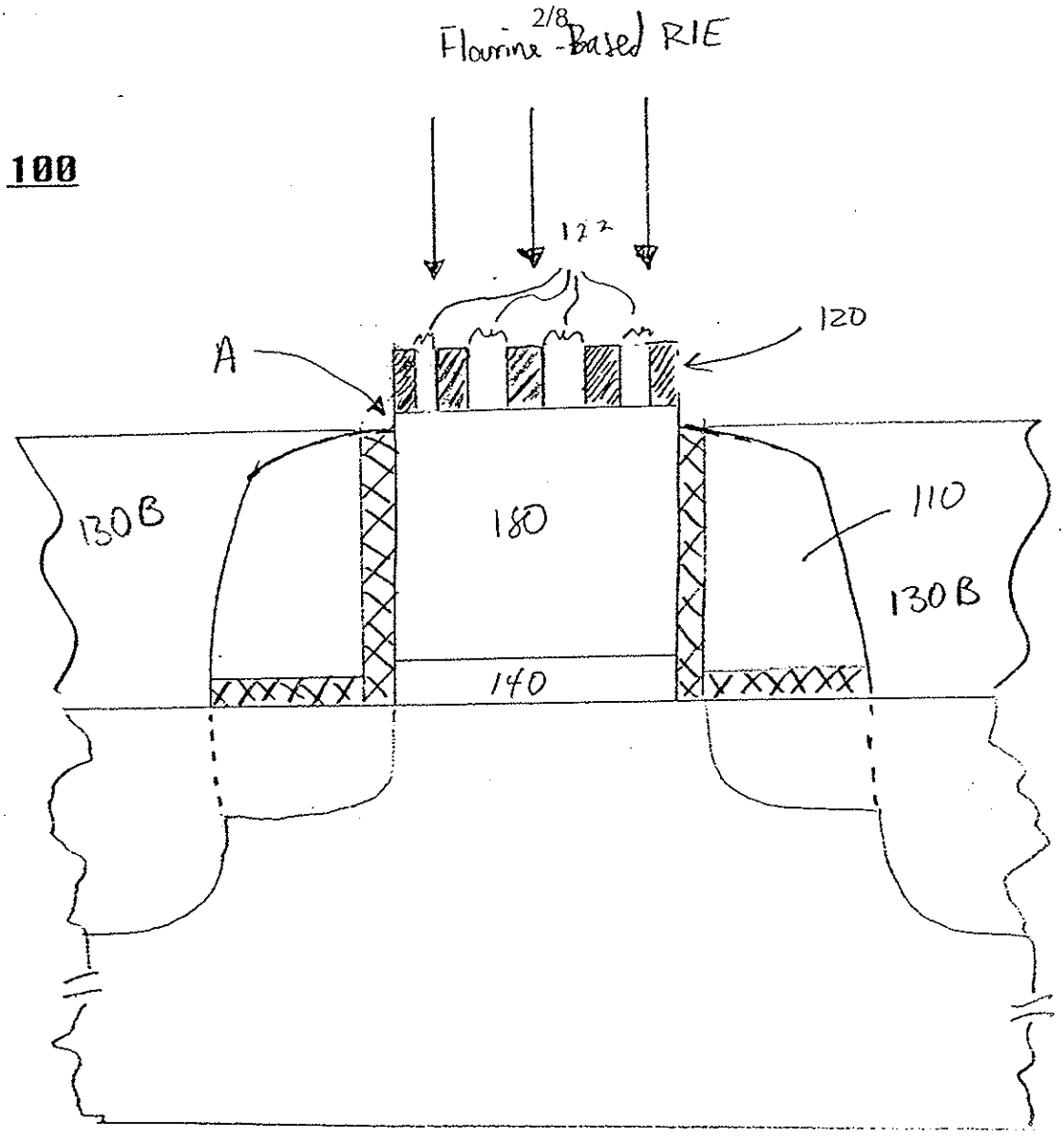


FIG. 2

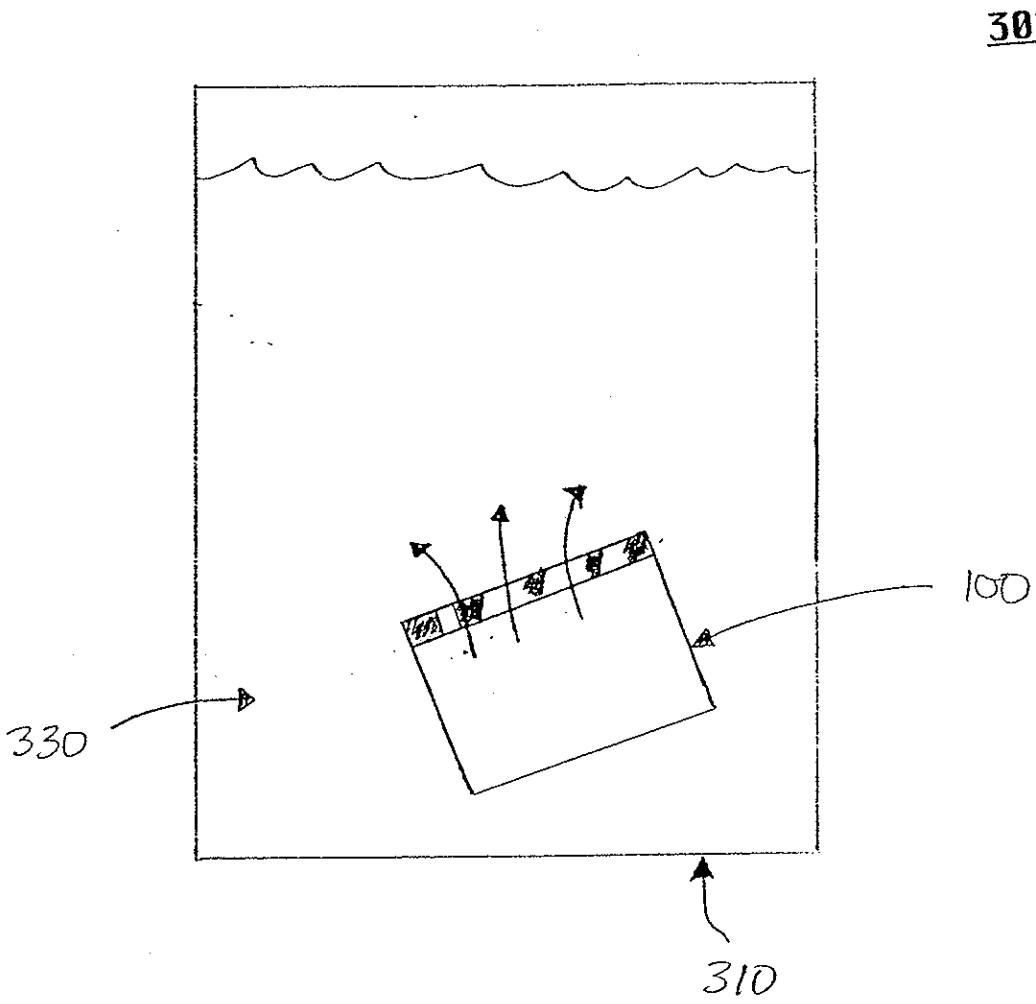


FIG. 3A

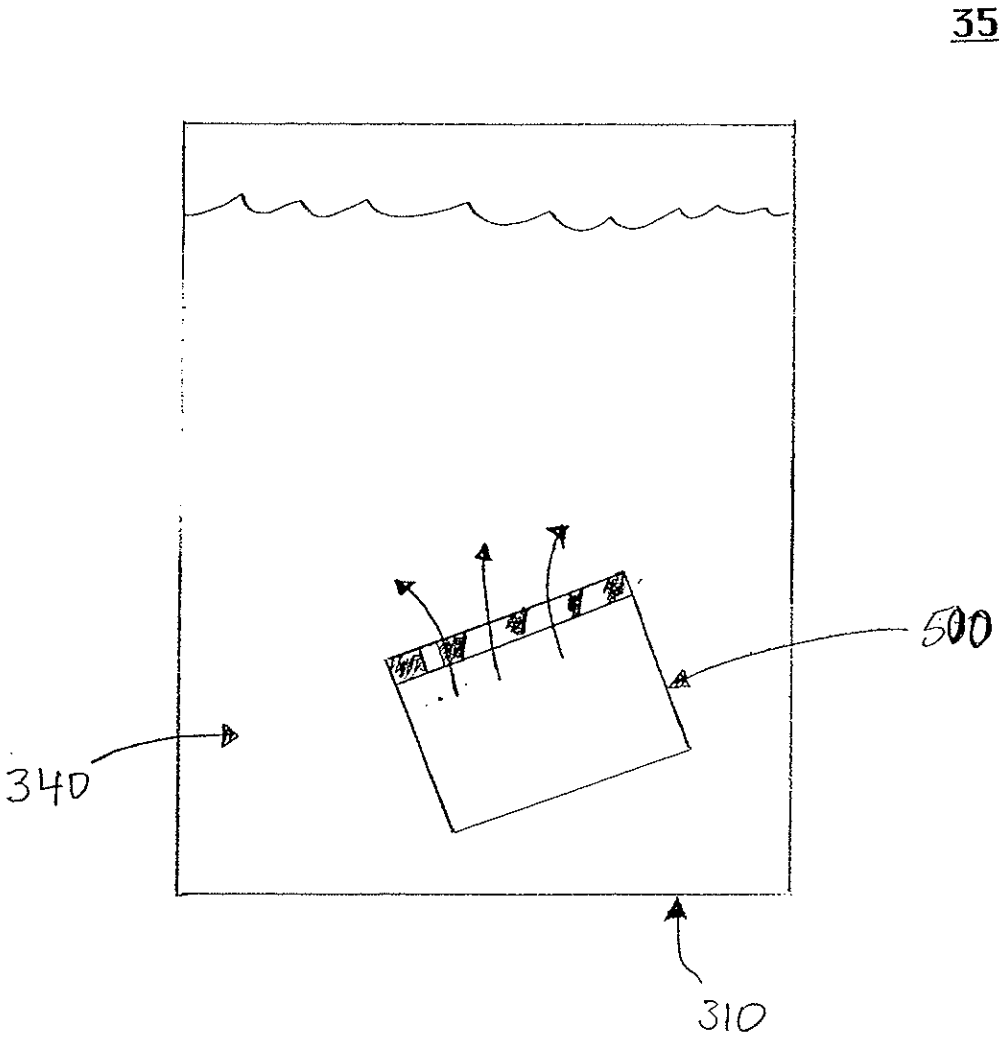


FIG. 3B

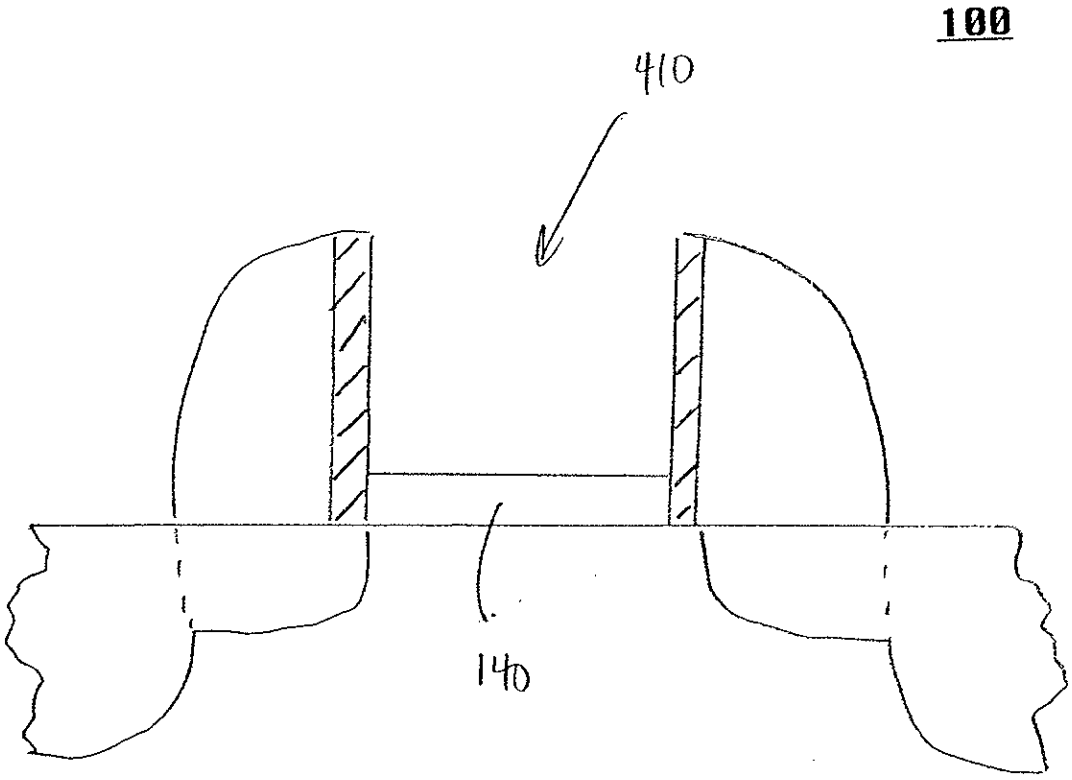


FIG. 4

500

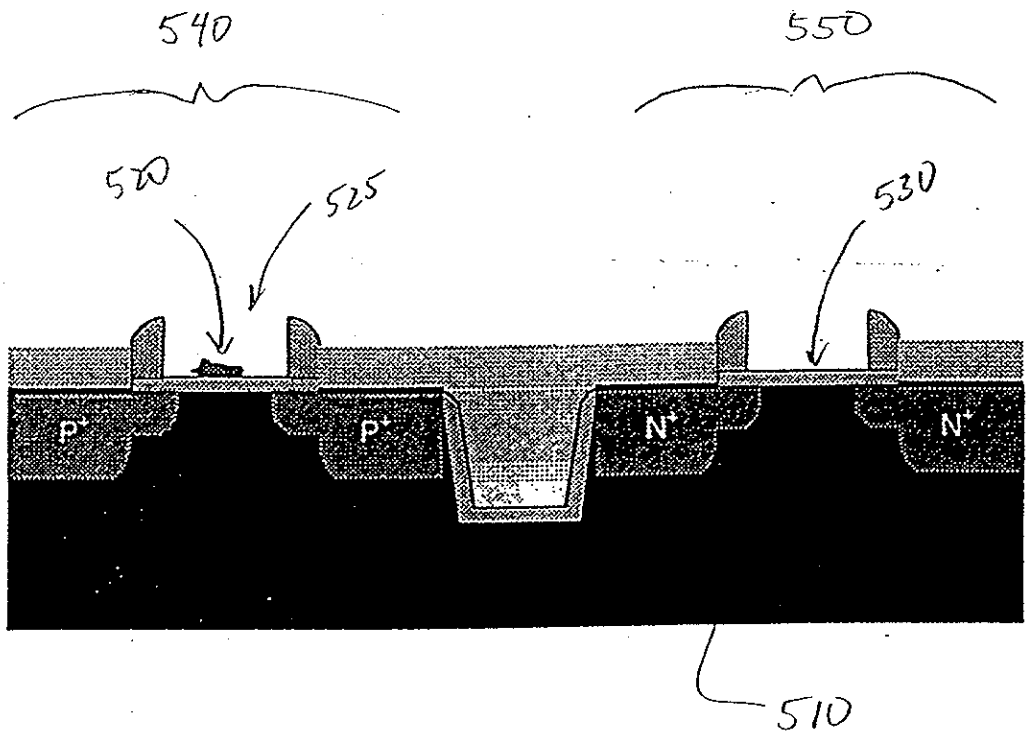


FIG. 5A

500

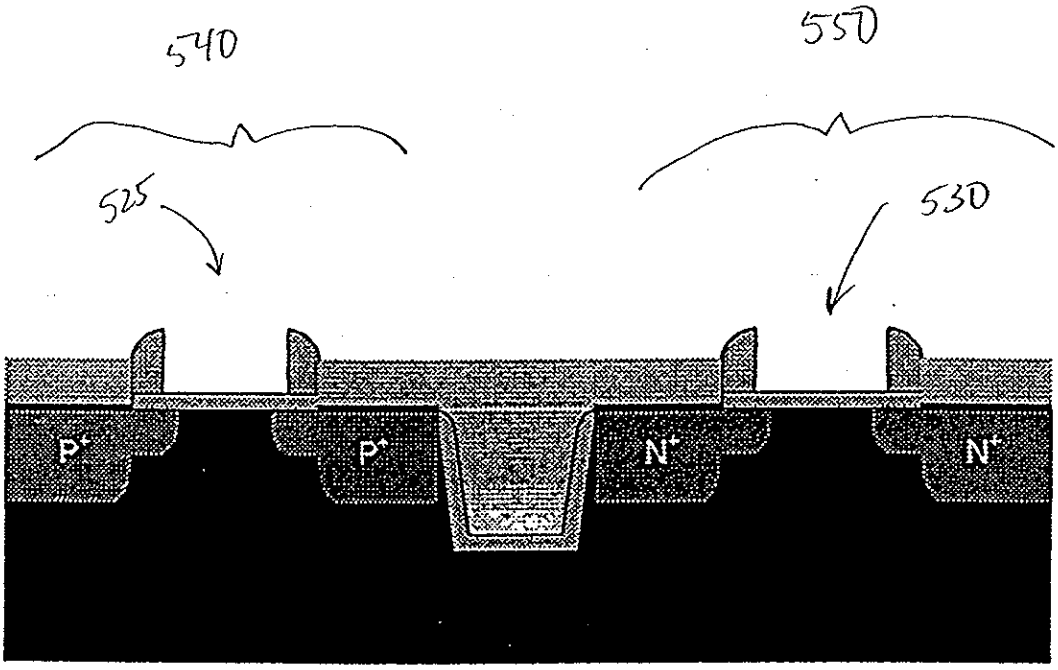


FIG. 5B

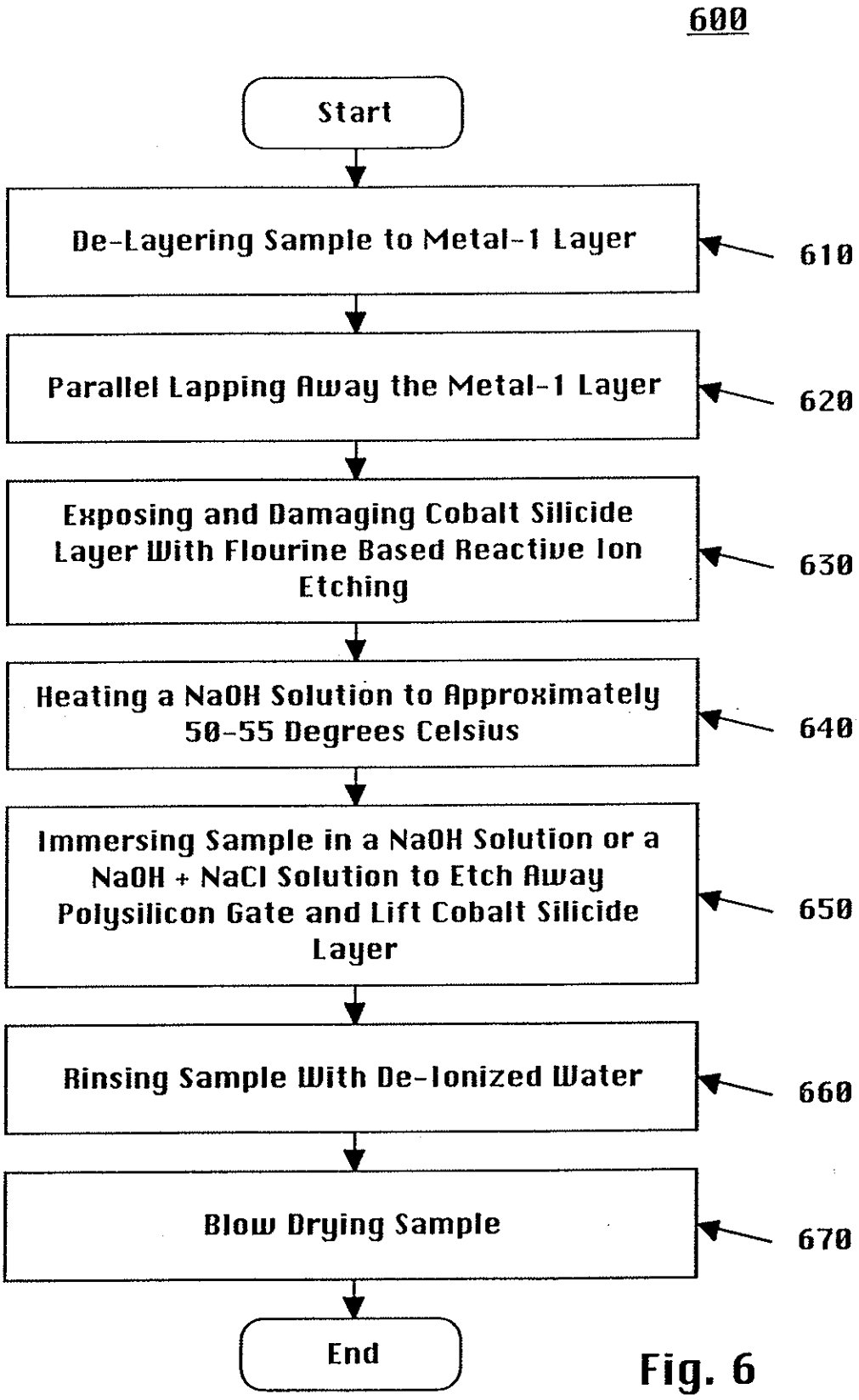

600
Start
De-Layering Sample to Metal-1 Layer
610
Parallel Lapping Away the Metal-1 Layer
620
Exposing and Damaging Cobalt Silicide Layer With Flourine Based Reactive Ion Etching
630
Heating a NaOH Solution to Approximately 50-55 Degrees Celsius
640
Immersing Sample in a NaOH Solution or a NaOH + NaCl Solution to Etch Away Polysilicon Gate and Lift Cobalt Silicide Layer
650
Rinsing Sample With De-Ionized Water
660
Blow Drying Sample
670
End

Fig. 6